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Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	1848080	semiconductor	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	NO	2007/08/17 07:38
S2	15461	semiconductor with island	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	N O	2007/08/16 12:53
83	173	semiconductor with island with recess	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	NO	2007/08/16 12:53
S	E.	S3 underetching	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	NO	2007/08/16 12:55
82	92	S3 etching	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND .	NO	2007/08/16 12:55
86	0	S5 high adj ohmic material	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	N O	2007/08/16 12:56

S7	1711	high adj ohm\$ material	US-PGPUB;	AND	NO	2007/08/16 12:56
			USPAT; EPO; JPO; DERWEN T.			
			I, IBM_TDB			
88	755	S7 semiconductor	US-PGPUB; USPAT;	AND	N O	2007/08/16 12:56
			EPO, JPO, DERWEN			
			T; IBM_TDB			
68	0	S7 S3	US-PGPUB; USPAT:	AND	NO	2007/08/16 12:56
			EPO; JPO; DERWEN			
	· ·	-	T; IBM_TDB			
S10	0	S3 high adj ohm\$ material	US-PGPUB; USPAT:	AND	N O	2007/08/16 12:57
			EPO; JPO; DERWEN			
			T; IBM_TDB			
S11	31	S7 semiconductor near6 island	US-PGPUB;	AND	N O	2007/08/16 12:58
			EPO; JPO; DERWEN			
			T; IBM_TDB			
S12	755	(high adj ohm\$ material) semiconductor	US-PGPUB;	AND	N O	2007/08/16 13:00
			EPO; JPO; DERWEN			
			T; IBM TDB			

(high adj ohm\$ material) semiconductor with island near15 recess (high adj ohm\$ material) semiconductor rear15 recess (high adj ohm\$ material) semiconductor rear15 recess (high adj ohm\$ material) semiconductor etch\$ (high adj ohm\$ material) semiconductor etch\$ (high adj ohm\$ material) semiconductor underetch\$ (high adj ohm\$ semiconductor underetch\$ (high a

S19	4	"2003045119"	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	N O	2007/08/16 13:15
S20	13	wang hsiao adj lei	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	Z O	2007/08/16 13:29
S21	15	"3715232"	US-PGPUB, USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	N O	2007/08/16 13:29
S22	4	"5972758"	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	N O	2007/08/16 15:56
S23	43930	semiconductor with trench	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	Z O	2007/08/17 07:38
S24	6707	semiconductor with trench with dielectric	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	N O	2007/08/17 07:38

2007/08/17 07:46	2007/08/17 08:07	2007/08/17 08:07	2007/08/17 08:08	2007/08/17 08:08	2007/08/17 08:08
NO NO	NO	NO NO	NO	NO	NO
AND	AND	AND	AND	AND	AND
US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB
semiconductor with trench with dielectric with groove	3 semiconductor with trench with dielectric with groove with high adj conductiv\$	semiconductor with silicon with germanium	semiconductor with (silicon with germanium layer)	semiconductor with (mixed crystal with silicon with germanium layer)	386 semiconductor with (mixed crystal with silicon with germanium layer) with germanium
S25	S26	S27	S28	S29	S30

5	,		41.40	4.5	:	
66	n	semiconductor with (mixed crystal with silicon with germanium layer) with trench	US-PGPUB; USPAT; EPO; JPO; DERWEN	AND	Z O	
			I; IBM_TDB			
S32	~	semiconductor with (mixed crystal with silicon with germanium layer) with groove	US-PGPUB; USPAT; EPO; JPO; DERWEN	AND	N O	2007/08/17 12:43
			I; IBM_TDB			
S33	283	semiconductor with multiple devices with groove	US-PGPUB; USPAT; EPO; JPO; DERWEN	AND	NO	2007/08/17 12:44
			iBM_TDB			
S34	0	semiconductor with (mixed crystal with silicon with germanium layer) with multiple devices with groove	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	Z O	2007/08/17 12:43
S35	64	semiconductor with multiple devices with groove and anisotropic etching	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	NO	2007/08/17 12:45
S36	901649	semiconductor with multiple devices with groove or cavity	US-PGPUB; USPAT; EPO; JPO; DERWEN T; IBM_TDB	AND	NO	2007/08/17 12:51

S37	137	semiconductor with multiple devices with groove and cavity	US-PGPUB; AND	AND	NO	2007/08/17 12:53
			USPAT;			
			EPO; JPO;			
			DERWEN			-
			Ë			
			IBM_TDB			